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(71)Applicant : TOKYO ELECTRON LTD

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(72)Inventor : HASEBE KAZUhide
SATO SHOICHI
UMEZAWA KOUTAI

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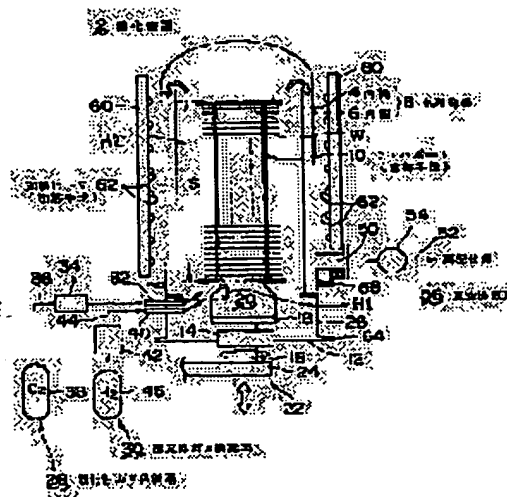
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(54) METHOD OF OXIDIZING MEMBER TO BE TREATED AND OXIDIZING EQUIPMENT

(57)Abstract:

PROBLEM TO BE SOLVED: To provide a method of oxidizing members to be treated, which can raise both the in-plane uniformity of an oxide film and the characteristics of the film quality of the oxide film while the oxidizing rate of the oxide film is highly maintained to a certain degree.

SOLUTION: In a method of oxidizing members W to be treated for oxidizing the surfaces of the members W to be treated set at a prescribed temperature in a treating container 8 put under a vacuum atmosphere, the surfaces of the members W to be treated are oxidized using hydroxyl group active species and oxygen species as the main body of a catalyst. As a result, while the oxidizing rate of the oxide film is highly maintained to a certain degree, both the in-plane uniformity of the oxide film and the characteristics of the film quality of the oxide film are raised.



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